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1 Influence of plasma treatment and cleaning on vacuum wafer bonding

Wei Bo Yu; Cher Ming Tan; Jun Wei; Shu Sheng Deng; Mui Ling Nai;

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[PDF Full-Text (772 KB)] [Abstract]

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#### 5 Material properties of plasma-thinned bonded SOI wafers

Feng, T.; Matloubian, M.; Mathur, D.P.; Mumola, P.B.; Gardopee, G.J.; SOI Conference, 1993. Proceedings., 1993 IEEE International, 5-7 Oct. 1993 Pages:62 - 63

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